



Keisaku Yamada

Keisaku Yamada received the Ph.D. degree in engineering from Waseda University in 1979.

From 1979 to 2002, he worked at the IC and ULSI Research Center, Toshiba Corporation in Kanagawa, Japan, where he studied diffusion, CVD, PVD process technologies in MOS for ULSI's and TFT for display.

He joined the Nanotechnology Research Laboratory of Waseda University in Tokyo, Japan, in 2002. His current research is the thermodynamics in silicon process. In 1986, he started the study of HfO₂ application technology for LSI's.

Dr. Yamada is a member of the Japan Society of Applied Physics Society.